

Electronic Patent Application Fee Transmittal

Application Number:	10578683			
Filing Date:	09-May-2006			
Title of Invention:	FABRICATION METHOD OF EXTREME ULTRAVIOLET RADIATION MASK MIRROR USING ATOMIC FORCE MICROSCOPE LITHOGRAPHY			
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Attorney Docket Number:	05823.0283			
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Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
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Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Post-Allowance-and-Post-Issuance:				
Utility Appl issue fee	2501	1	755	755
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Total in USD (\$)				1055